Plasma Sources Science and Technology

PURPOSE-LED PUBLISHING™

CORRIGENDUM

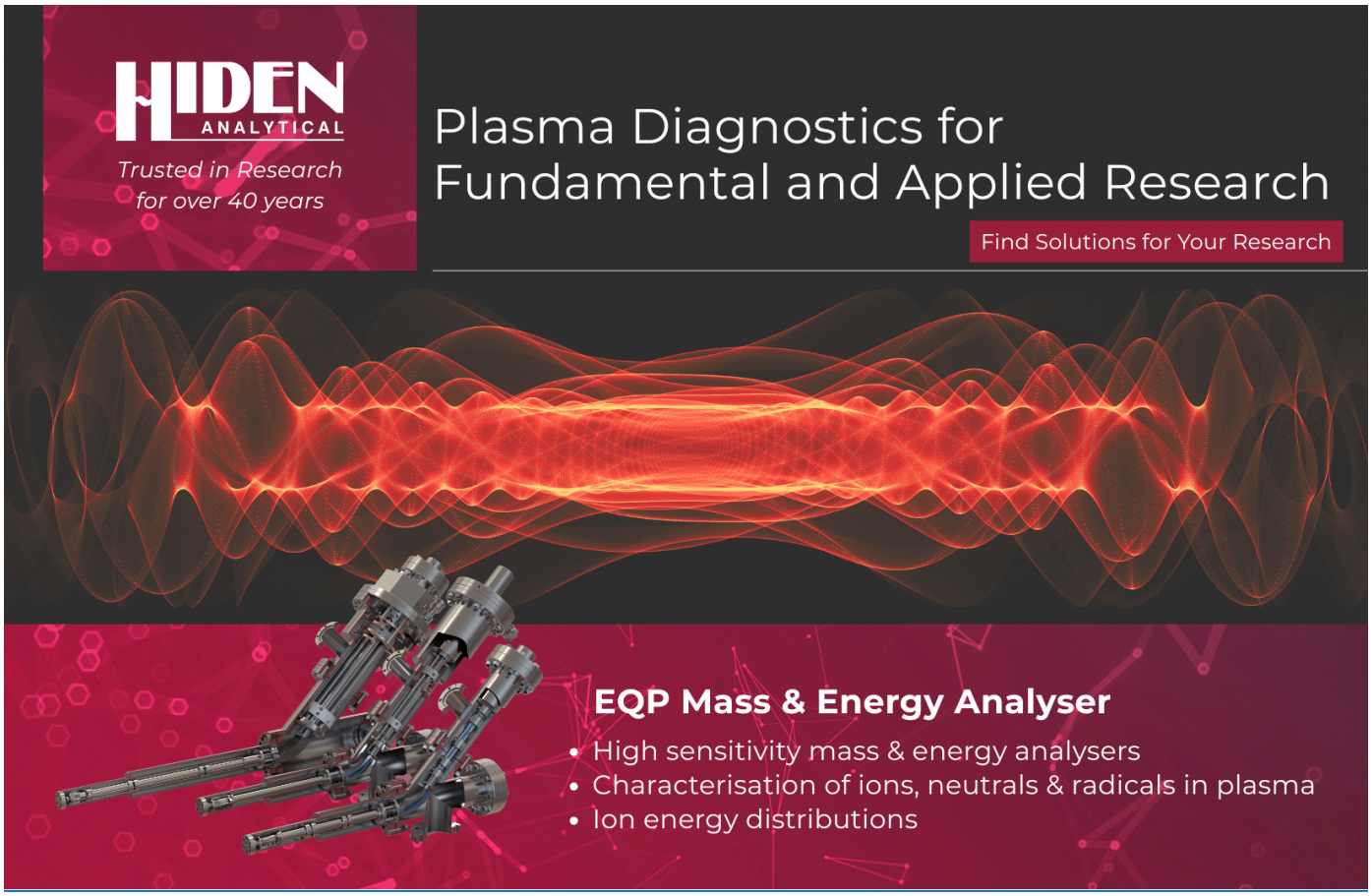
CORRIGENDUM: Control of axial direction electron temperature distribution by gradient DC magnetic field in inductively coupled plasma (2025 *Plasma Sources Sci. Technol.* 34 035010)

To cite this article: Yi-Lang Jiang *et al* 2026 *Plasma Sources Sci. Technol.* **35** 099502

View the article online for updates and enhancements.

You may also like

- Spatially resolved methane decomposition in a short glow discharge: insights into suprathermal hydrogen and radical chemistry
Shurik Yatom
- Self-consistent diffusion modeling of precursor plasma and neutral dynamics in the CRAFT RF-driven negative ion source
Stepanov D S, Xufeng Peng, Bo Liu et al.
- CORRIGENDUM: Low-damage etching of poly-Si and SiO_2 via a low-energy electron beam in inductively coupled CF_4 plasma (2024 *Plasma Sources Sci. Technol.* 33 105013)
Jiwon Jung, Jae-Hwi Kim, Chang-Min Lim et al.



This content was downloaded from IP address 166.104.66.192 on 13/10/2026 at 01:59

Plasma Sources Science and Technology

Check for updates

RECEIVED
15 July 2026

ACCEPTED FOR PUBLICATION
29 July 2026

PUBLISHED
10 September 2026

CORRIGENDUM

CORRIGENDUM: Control of axial direction electron temperature distribution by gradient DC magnetic field in inductively coupled plasma (2025 *Plasma Sources Sci. Technol.* **34** 035010)

Yi-Lang Jiang[1], You He[1], Beom-Jun Seo[1], Myoung-Jae Lee[2], Ju-Ho Kim[1,*] and Chin-Wook Chung[1,*]

[1] Department of Electrical Engineering, Hanyang University, 17 Haengdang-dong, Seongdong-gu, Seoul 133-791, Republic of Korea
[2] Department of Physics, Hanyang University, 17 Haengdang-dong, Seongdong-gu, Seoul 133-791, Republic of Korea
[*] Authors to whom any correspondence should be addressed.

E-mail: electrickjh@gmail.com and joykang@hanyang.ac.kr

In the original version of this article, the Acknowledgment section on p. 11 contains an incorrect Grant Number (RS-2023-00237362). The grant number should be revised to RS-2023-00237543. Therefore, the Acknowledgment should be revised as below:

Acknowledgments

This work was supported by the National Research Foundation of Korea (NRF) grant funded by the Korean government (MSIT) (No. RS-2023-00260527), the Ministry of Trade, Industry & Energy (MOTIE) (20020392, 20022472, 1415187403, 20024017, 20012609, 20018982, 2410003887, 1415187722, 00154752, and 1415187459), and Korea Semiconductor Research Consortium (KSRC) (RS-2023-00237543, RS-2023-00235950, and RS-2023-00236642).

Following are the results of a study on the 'Leaders in Industry University Cooperation 3.0' Project, supported by the Ministry of Education and National Research Foundation of Korea.

This correction does not alter the contents of this article including the results, discussions, and conclusions.

Data availability statement

No new data were created or analysed in this study.

ORCID iD

Chin-Wook Chung 0000-0002-7771-6547

© 2026 IOP Publishing Ltd. All rights, including for text and data mining, AI training, and similar technologies, are reserved.